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ttorney's Docket No. 5308-156

28118 PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

n re: Ryu et al.

Serial No.: 09/911,995

Filed: July 24, 2001

Group Art Unit: 2811 Confirmation No.: 5240

Examiner: Gene M. Munson

For:

JAN 2 2 2004

SILICON CARBIDE POWER METAL-OXIDE SEMICONDUCTOR FIELD

EFFECT TRANSISTORS HAVING A SHORTING CHANNEL AND METHODS OF FABRICATING SILICON CARBIDE METAL-OXIDE SEMICONDUCTOR FIELD EFFECT TRANSISTORS HAVING A

SHORTING CHANNEL

Date: January 20, 2004

Commissioner for Patents PO Box 1450 Alexandria, VA 22313

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

Attached is a list of documents on form PTO-1449 together with copies of each identified document. This Information Disclosure Statement is submitted in accordance with 37 C.F.R. § 1.97(c), before final Office Action or Allowance, whichever is earlier.

Please find attached a check in the amount of \$180.00 for the fee specified in 37 C.F.R. § 1.17(p). The Commissioner is authorized to charge any additional fee or credit any refund to Deposit Account No. 50-0220.

Respectfully submitted,

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FORM PTO		U.S. Department ent and Trademark		Attorney Docket Number 5308-156			Serial No. 09/911,995		
LIST	OF DO	OCUMENTS CITE	D BY APPLI	CANT					
PE (Les several sheets if necessary)									
	3 2007				Applicants:	Ryu et al			
U. S. PATENT DO					Filing Date: July 24, 2001			Group 2811	
TO THE	SALAS	,	U. S	S. PATENT DO	CUMENTS	-			
Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date if Appropriate	
	1	5,479,316	12/26/95	Smrtic et al.		361	322		
	2	5,739,564	04/14/98	Kosa et al.		257	298		
	3	6,228,720	05/08/01	Kitabatake et al.		438	268		
<b>'</b>	4	6,239,463	05/29/01	Schörner et al.		257	328		
3	5	6,316,791	11/13/01			257	77		
<u> </u>	6	6,593,620	07/15/03			257	335		
	7	6,610,366	08/26/03	Lipkin		427	378		
			FORE	IGN PATENT I	OOCUMENTS		_		
		Document Number	Date	Country		Class	Subclass	Translation Yes   No	
	8	WO98/02924	01/22/98	PCT					
	<b>,</b>	OTHER DOO	CUMENTS (I	ncluding Author	r, Title, Date, Pe	rtinent Pages	, Etc.)		
	9	Dimitrijev et al., "Nitridation of Silicon-Dioxide Films Grown on 6H Silicon Carbide", <i>IEEE Electronic Device Letters</i> , Vol. 18, No. 5, May 05, 1997, pp. 175-177.							
	De Mao et al., "Thermal Oxidation of SiC in N <sub>2</sub> O", J. Electrochem. Soc., Vol. 141, 1994, pp. L150-L1								
	11	Ryu et al., Article and Presentation: "27 mΩ-cm², 1.6 kV Power DiMOSFETs in 4H-SiC," <i>Proceedings</i> of the 14 International Symposium on Power Semiconductor Devices & ICs 2002, June 4-7, 2002, Santa Fe, NM.							
	Kobayashi et al. "Dielectric Breakdown and Current Conduction of Oxide/Nitride/Oxide Structures," 1990 IEEE Symposium on VLSI Technology. pp. 119-120.								
	13	Ma et al. "Fixed and trapped charges at oxide-nitride-oxide heterostructure interfaces formed by remote plasma enhanced chemical vapor deposition," <i>J. Vac. Sci. Technol. B.</i> Vol. 11, No. 4, Jul/Aug 1993, pp. 1533-40.							